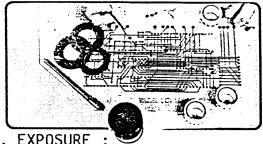
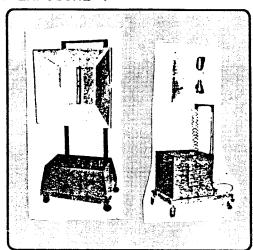


## COPPER FOIL SHEET PHOTORESIST P.W.B. INSTRUCTION

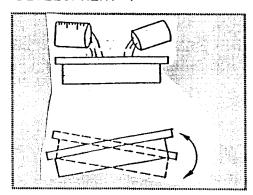
## 1. ARTWORK(A/W) PREPARE :



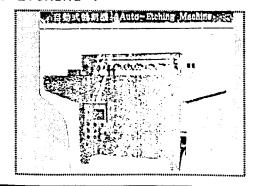
2. EXPOSURE



3. DEVELOPMENT :



4. ETCHING:



- A. HANDMAKE BY USING TRANSFER PAPER TYPE ON DRAWING FILM.
- B. BY COMPUTER CAD/CAM & PLOTER DRAWING ...etc.
- A. TAKE OFF THE BLACK PROTECTING MEMBRANCE FORM PHOTORESIST SHEET BEFORE EXPOSURE.
- B. A/W MUST BE INDENSE TO CLOSE THE COPPER FOIL SHEET BEFORE EXPOSURE.
- C. EXPOSING TIME & DISTANCE....
  - a. 6-10 MINUTES AT 4-6 cm (by FLOURESCEN LAMP)
  - b. 60-90 SECONDS AT 40-80 cm (by CARBON-ARC LAMP)

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- A. DEVELOPER 50 g, water 1,000 cc AT TEMP. 15-35℃ (1 : 20) as DEVELOPING SOLUTION.
- B. DEVELOPING TIME..... 0.5-2 MINUTES.
- C. CLEAN WITH CLEAN WATER AFTER DEVELOPMENT.
- D. DRY IT AFTER CLEAN.
- A. ETCHING SOLUTION CHLORIDE IRON + WATER (46:54) AT 35℃
- B. ETCHING MACHINE ( ETCHING TIME 4-10 MINUTES)OR PLASTIC TANK (ETCHING TIME 20-50 MINUTES ).
- C. WATER CLEAN & DRY AFTER ETCHED